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Titolo	Short wavelength laboratory sources : principles and practices / / edited by Davide Bieiner [and five others]
Pubbl/distr/stampa	Cambridge, England : , : Royal Society of Chemistry, , 2015 ©2015
ISBN	1-84973-501-8
Descrizione fisica	1 online resource (468 p.)
Disciplina	537
Soggetti	Radiation sources X-rays
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references at the end of each chapters and index.
Nota di contenuto	CONTENTS; ATOMIC AND PLASMA PHYSICS SOFTWARE AND DATABASES FOR THE SIMULATION OF SHORT WAVELENGTH SOURCES ; MODELLING OF PLASMA-BASED SEEDED SOFT X-RAY LASERS ; FIELD COHERENCE OF EUV SOURCES ; REACHABLE EXTREME ULTRAVIOLET WAVELENGTHS ACCORDING TO ELEMENTS/ATOMIC DATA ; ABSORPTION OF SHORT PUMPING PULSES FOR GRAZING INCIDENCE PUMPED X-RAY LASERS ; THEORETICAL ANALYSIS AND EXPERIMENTAL APPLICATIONS OF X-RAY WAVEGUIDES ; TABLE-TOP SOFT X-RAY Ar+8 LASERS EXCITED BY CAPILLARY Z-PINCHES ; NANOMETRE SCALE TAPERED PLANAR WAVEGUIDES FOR FOCUSING X-RAY FEMTOSECOND PULSES EXTREME ULTRAVIOLET EMISSION FROM MULTI-CHARGED STATE IONS IN POTASSIUM PLASMAS LASER PRODUCED PLASMA X-RAY AND EUV SOURCES FOR LITHOGRAPHY ; PRACTICAL ASPECTS OF XUV GENERATION BY NON-LINEAR FREQUENCY CONVERSION ; ELECTRON TRAJECTORIES IN HIGH HARMONIC GENERATION ; MODIFIED CATHODE TUBE: X-RAY AND XUV RADIATION FOR NANO-INSPECTION ; CHARACTERISTICS OF A SUB-PICOSECOND TITANIUM K SOURCE USING RELATIVISTICALLY INTENSE LASERS ; BREMSSTRAHLUNG X-RAY EMISSION IN ELECTRON-BEAM-PUMPED K8F LASERS ; THE BERN ADVANCED GLASS LASER FOR EXPERIMENT (BEAGLE) X-RAY LASER FACILITY

ENEA EXTREME ULTRAVIOLET LITHOGRAPHY MICRO-EXPOSURE TOOL: MAIN FEATURES CHARACTERISATION AND MITIGATION OF IONS AND PARTICULATE EMITTED BY SOURCES FOR EXTREME ULTRAVIOLET LITHOGRAPHY ; EUV MULTILAYER OPTICS: DESIGN, DEVELOPMENT AND METROLOGY ; APPLICATIONS OF KrF LASERS FOR GENERATING COHERENT EUV RADIATION ; BROADBAND MULTILAYERS: TAILOR MADE MIRRORS FOR LINEARLY POLARIZED X-RAYS FROM A LASER PLASMA SOURCE ; SHORT WAVELENGTH LABORATORY SOURCES FOR SEMICONDUCTOR INSPECTION AND FABRICATION ; CARBON-NANOTUBES FIELD EMITTER TO BE USED IN ADVANCED X-RAY SOURCE LASER - PLASMA EUV SOURCE FOR MODIFICATION OF POLYMER SURFACES A SUB-PICO SECOND PLASMA SOURCE FOR TIME-RESOLVED X-RAY MEASUREMENTS ; APPLICATION OF FOCUSED X-RAY BEAMS IN RADIATION BIOLOGY; TIME-RESOLVED X-RAY DIFFRACTION OF CRYOGENIC SAMPLES USING A LASER BASED PLASMA SOURCE ; NEAR-EDGE X-RAY ABSORPTION FINE STRUCTURE MEASUREMENTS USING A LABORATORY-SCALE XUV SOURCE ; NANOMETER SCALE IMAGING USING A DESK-TOP LASER PLASMA EUV SOURCE ; LASER-PLASMA EUV AND SOFT X-RAY SOURCES FOR MICROSCOPY APPLICATIONS ; NANOMETER SCALE IMAGING WITH TABLE-TOP EXTREME ULTRAVIOLET LASER DEVELOPMENT AND OPTIMIZATION OF LASER-PLASMA EXTREME ULTRAVIOLET AND SOFT X-RAY SOURCES FOR MICROSCOPY APPLICATIONS SUBJECT INDEX

Sommario/riassunto

Our ability to manipulate short wavelength radiation (0.01-100nm, equivalent to 120keV-12eV) has increased significantly over the last three decades. This has lead to major advances in applications in a wide range of disciplines such as: the life and medical sciences, including cancer-related studies; environmental science, including studies of pollution and its effects; archaeology and other cultural heritage disciplines; and materials science. Although expansion in application areas is due largely to modern synchrotron sources, many applications will not become widespread, and therefore rout

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Titolo	After Ethnos / Tobias Rees
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ISBN	9781478090854 1478090855
Descrizione fisica	1 online resource (193 p.)
Soggetti	Social Science / Anthropology / Cultural & Social Social sciences
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Formato	Materiale a stampa
Livello bibliografico	Monografia
Sommario/riassunto	For most of the twentieth century, anthropologists understood themselves as ethnographers. The art of anthropology was the fieldwork-based description of faraway others-of how social structures secretly organized the living-together of a given society, of how a people had endowed the world surrounding them with cultural meaning. While the poetics and politics of anthropology have changed dramatically over the course of a century, the basic equation of anthropology with ethnography-as well as the definition of the human as a social and cultural being-has remained so evident that the possibility of questioning it occurred to hardly anyone. In After Ethnos Tobias Rees endeavors to decouple anthropology from ethnography-and the human from society and culture-and explores the manifold possibilities of practicing a question-based rather than an answer-based anthropology that emanates from this decoupling. What emerges from Rees's provocations is a new understanding of anthropology as a philosophically and poetically inclined, fieldwork-based investigation of what it could mean to be human when the established concepts of the human on which anthropology has been built increasingly fail us.